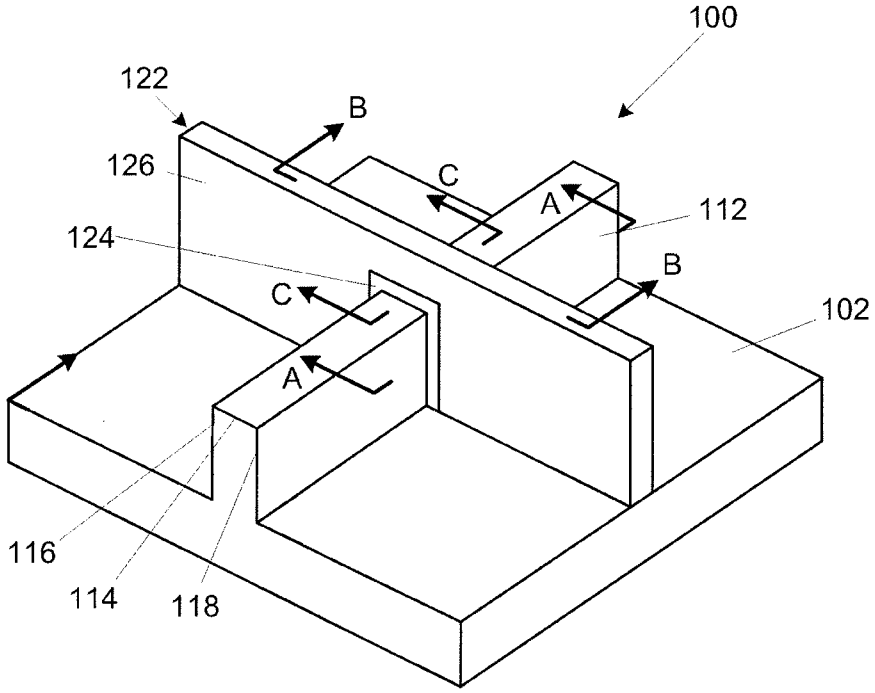


FIG. 1

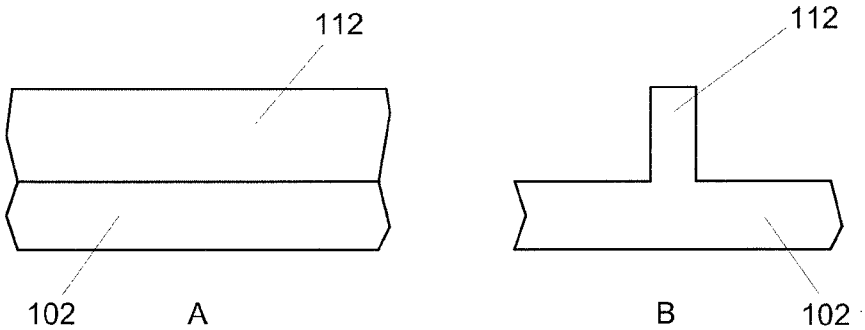


FIG. 2

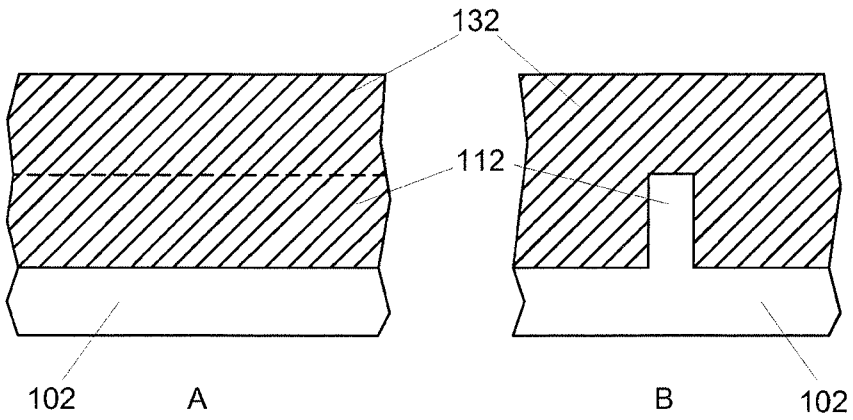


FIG. 3

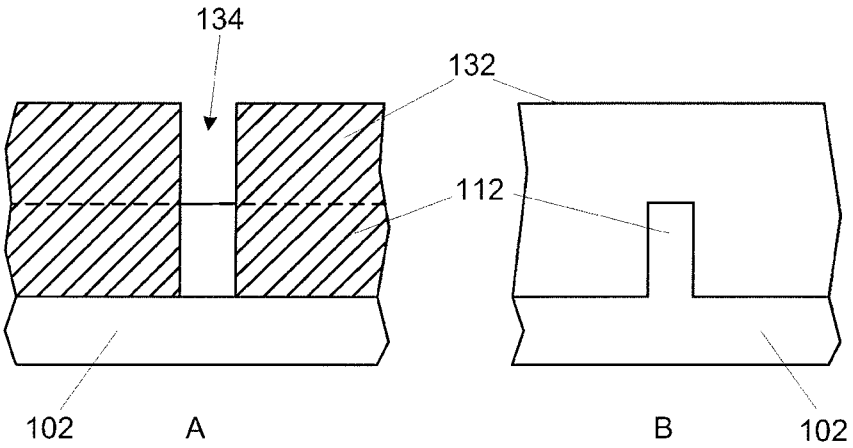


FIG. 4

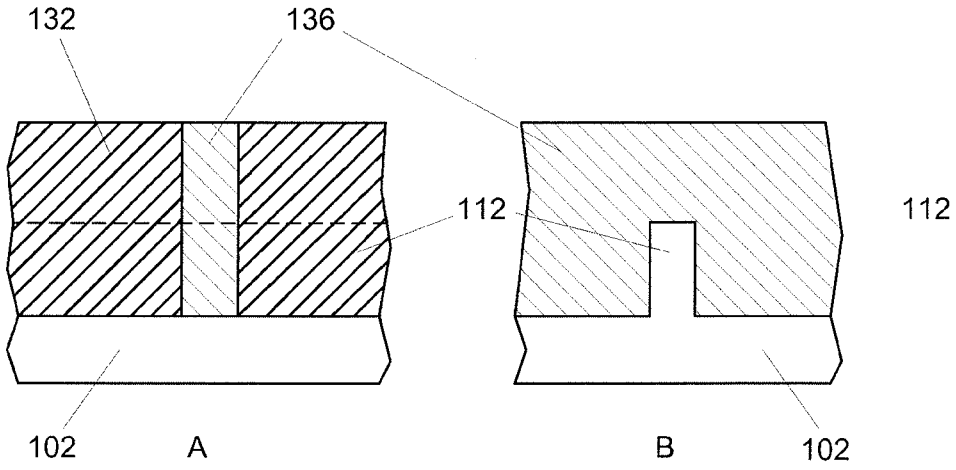


FIG. 5

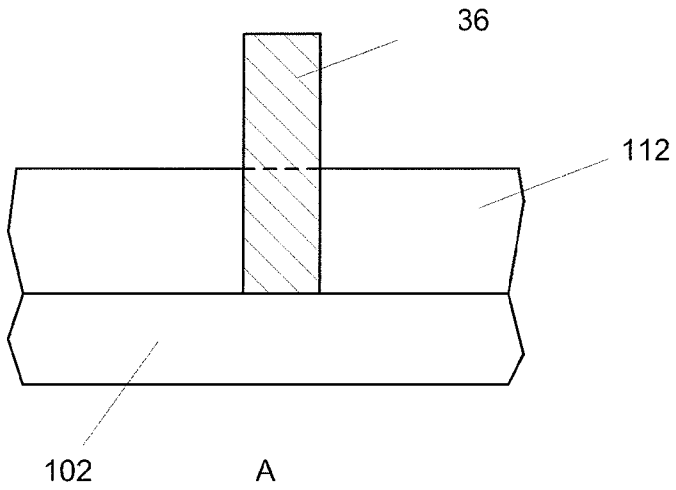


FIG. 6

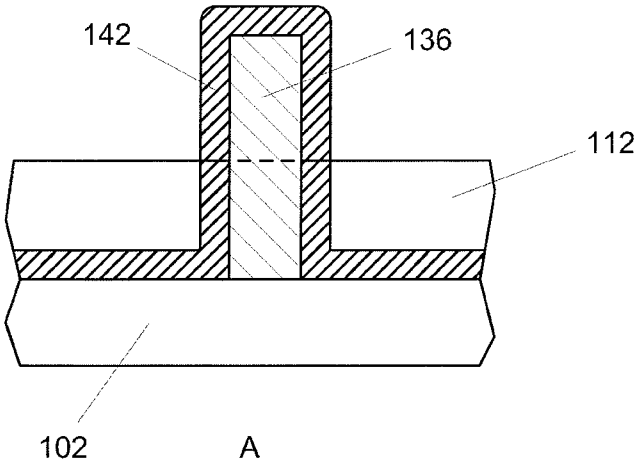


FIG. 7

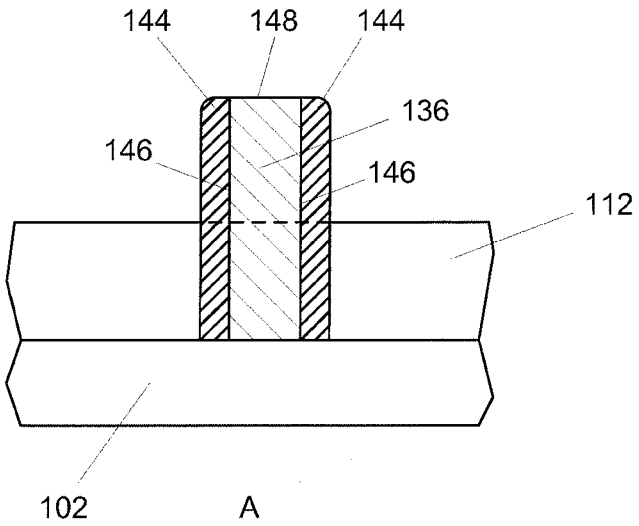


FIG. 8

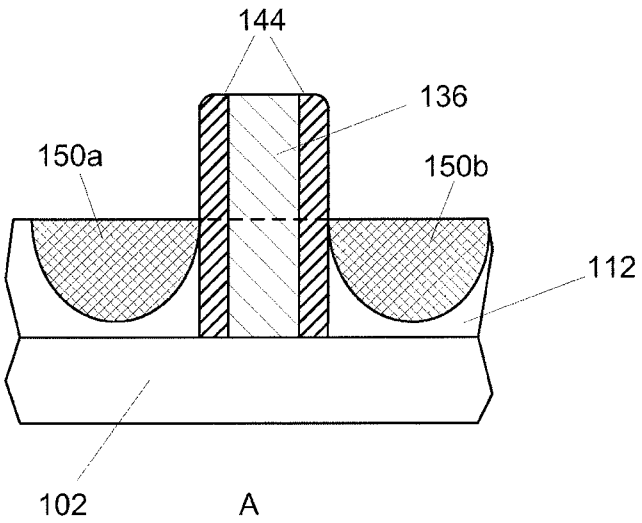


FIG. 9

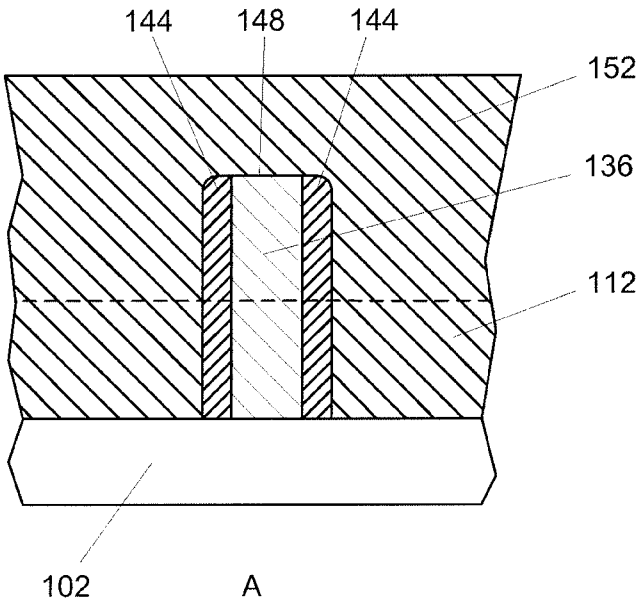


FIG. 10

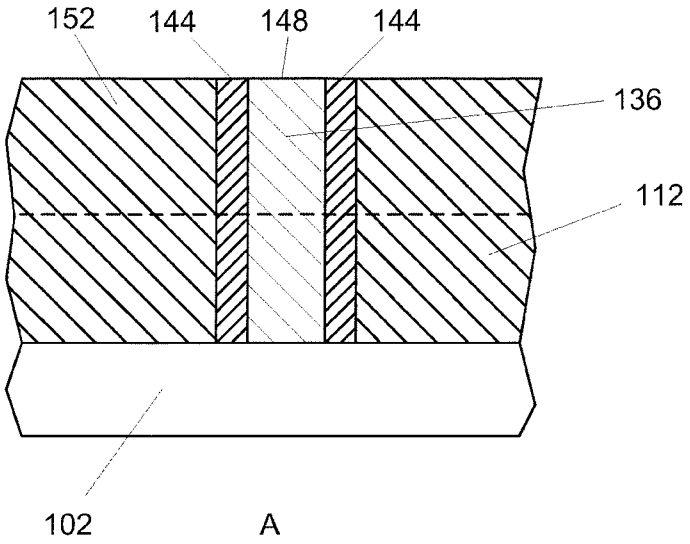


FIG. 11

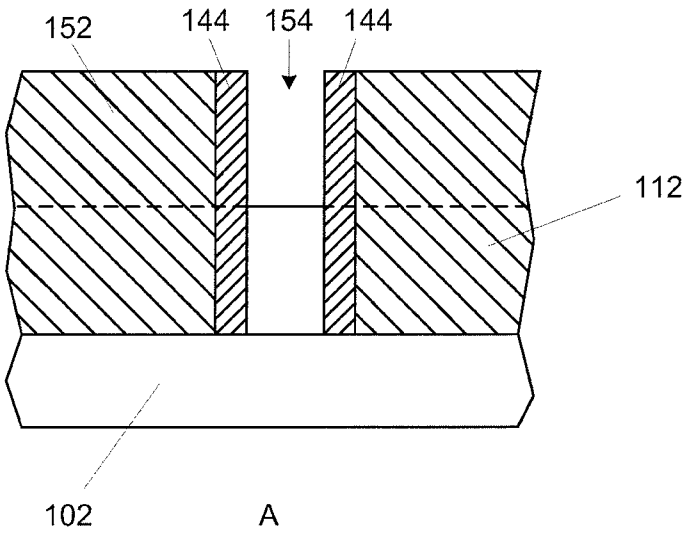


FIG. 12

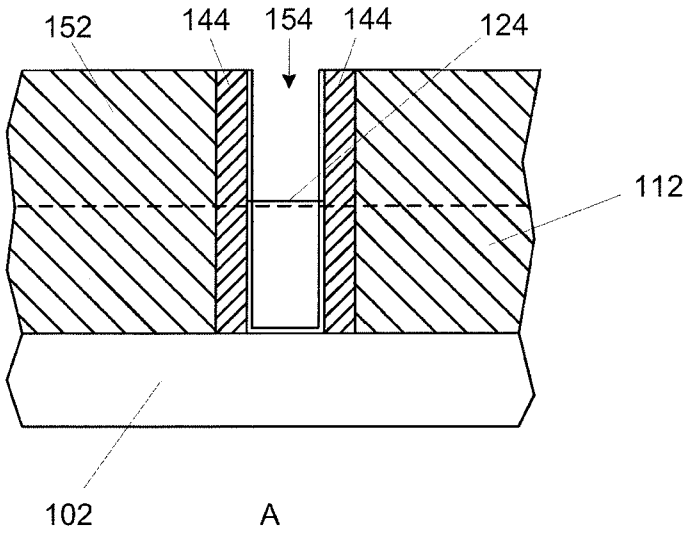


FIG. 13

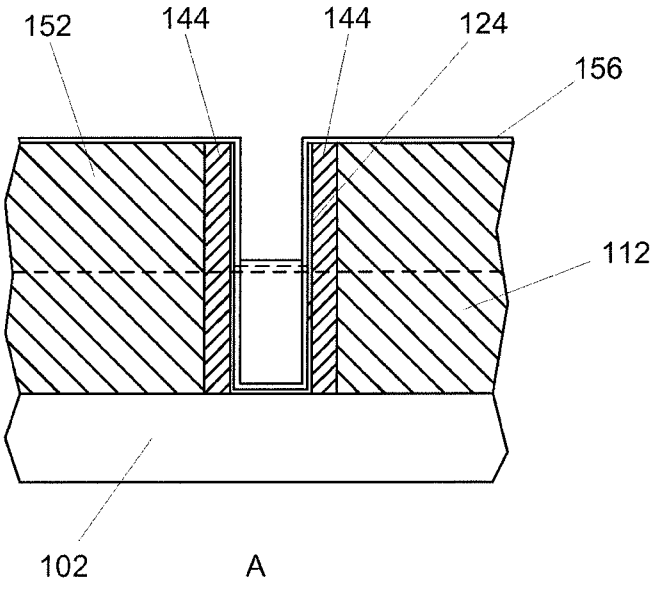


FIG. 14

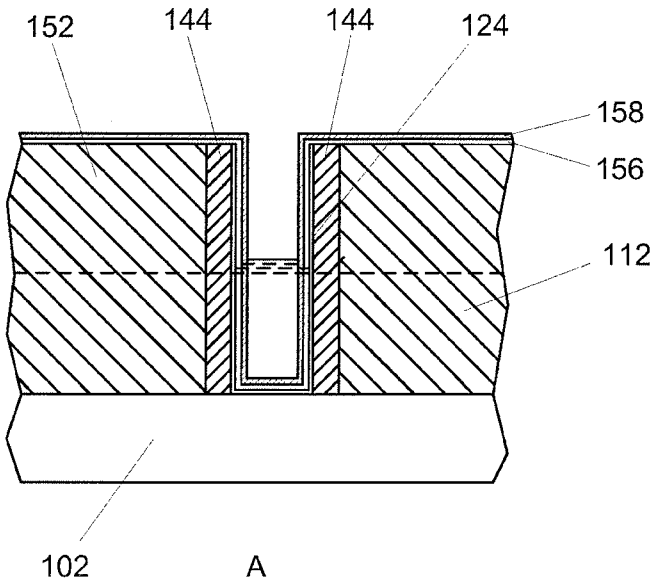

152
144
144
124
158
156
112
102
A

FIG. 15

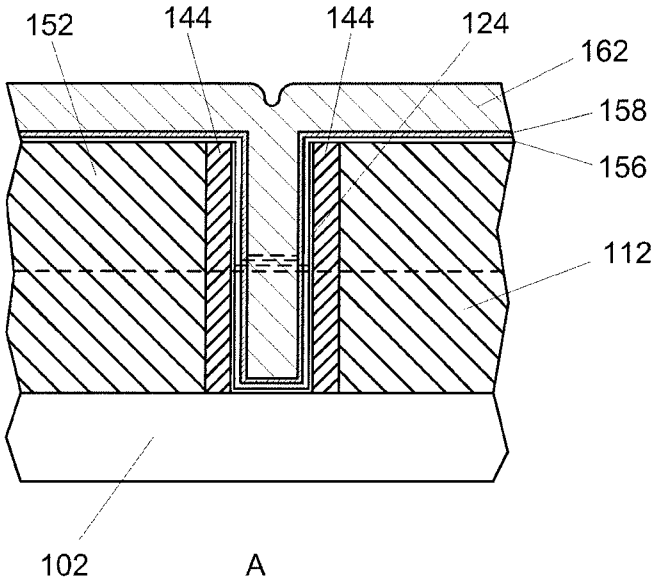

152
144
144
124
162
158
156
112
102
A

FIG. 16

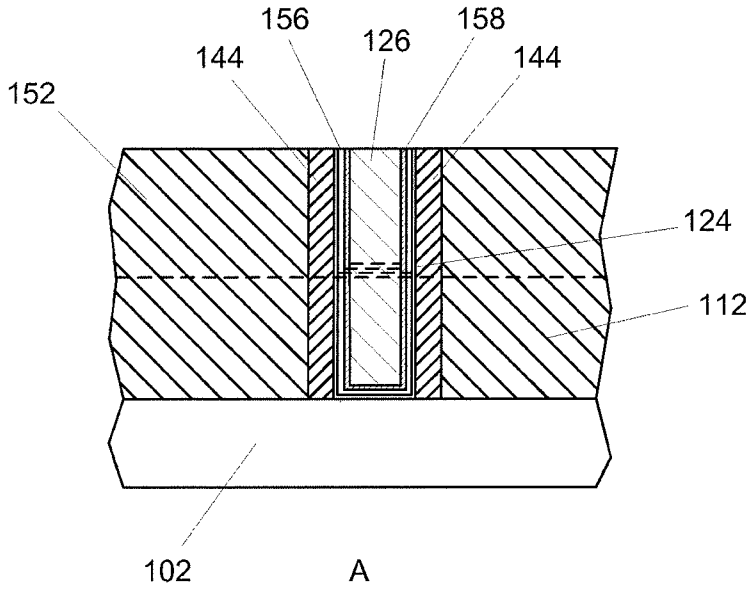

156
158
126
144
144
152
124
112
102
A

FIG. 17

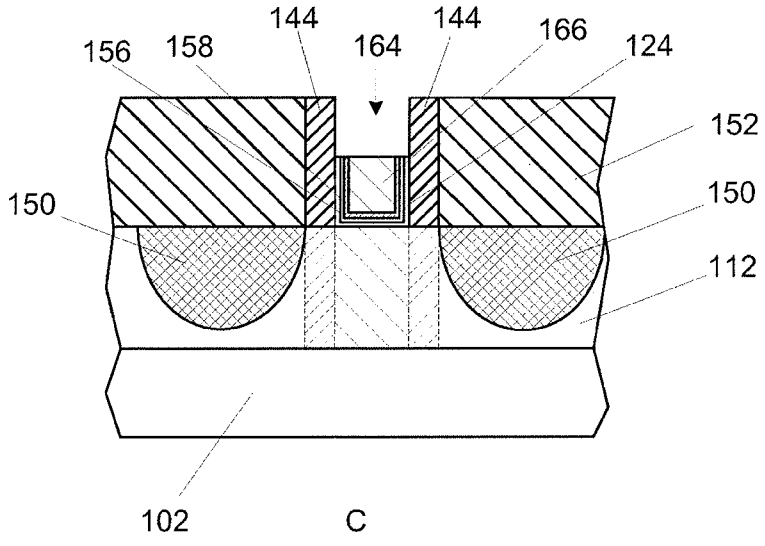

144
144
166
156
158
164
124
152
150
150
112
102
C

FIG. 18

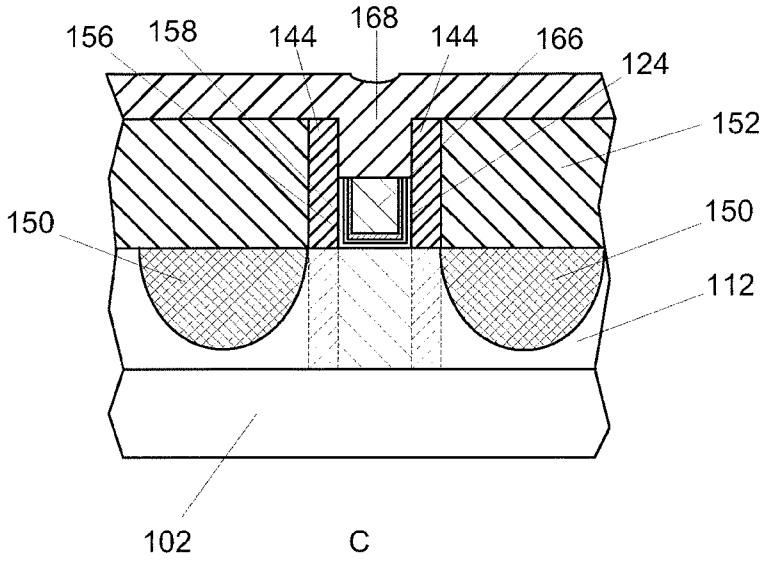

156
158
144
168
144
166
124
152
150
150
112
102
C

FIG. 19

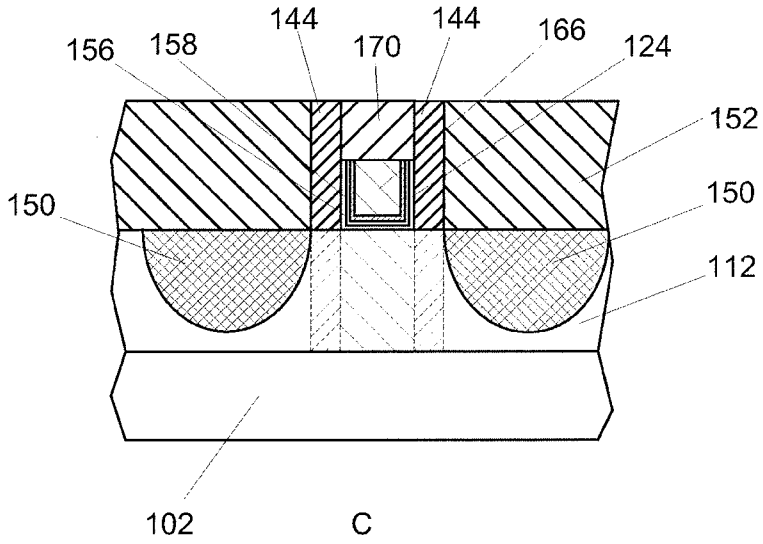

144
156
158
170
144
166
124
152
150
150
112
102
C

FIG. 20

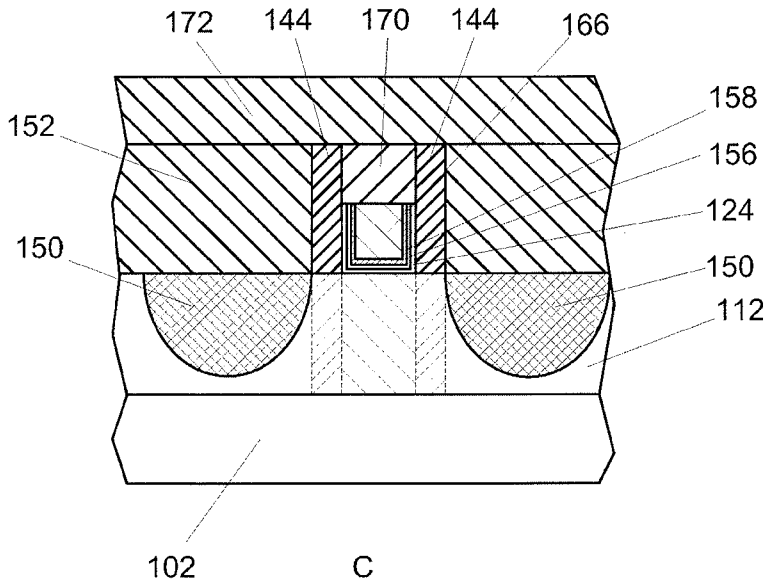

172
144
170
144
166
158
152
156
124
150
150
112
102
C

FIG. 21

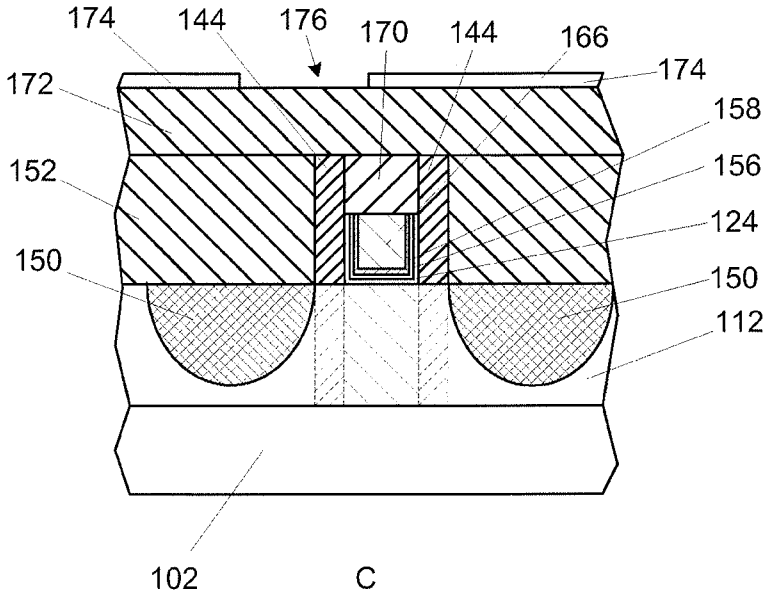

174
144
176
170
144
166
174
172
158
152
156
124
150
150
112
102
C

FIG. 22

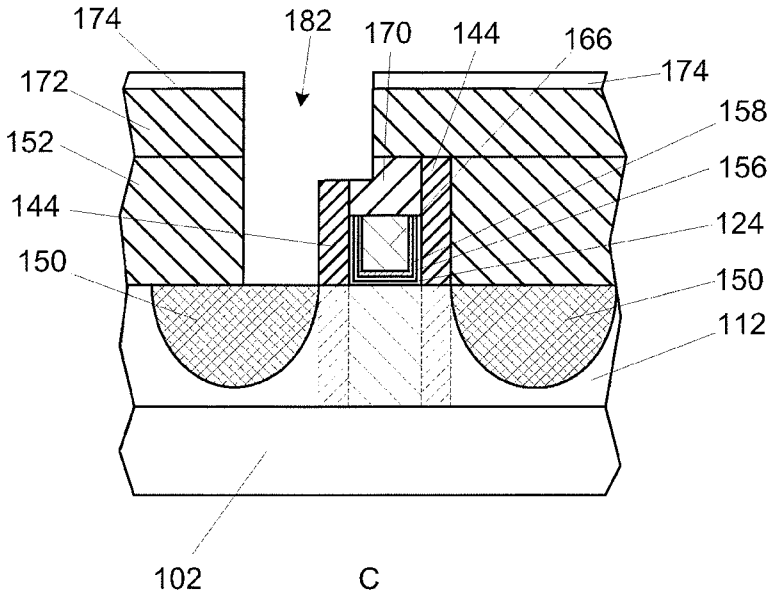

174
182
170
144
166
174
172
158
152
156
144
124
150
150
112
102
C

FIG. 23

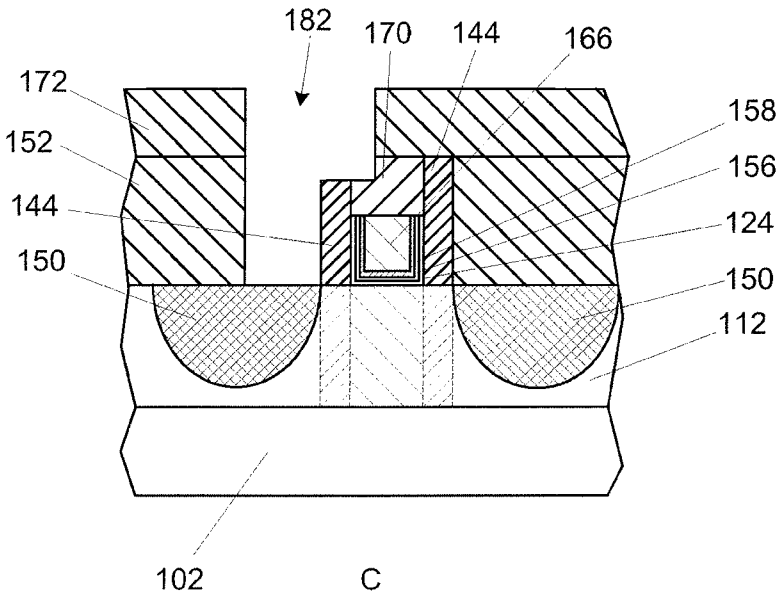

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170
144
166
172
158
152
156
144
124
150
150
112
102
C

FIG. 24

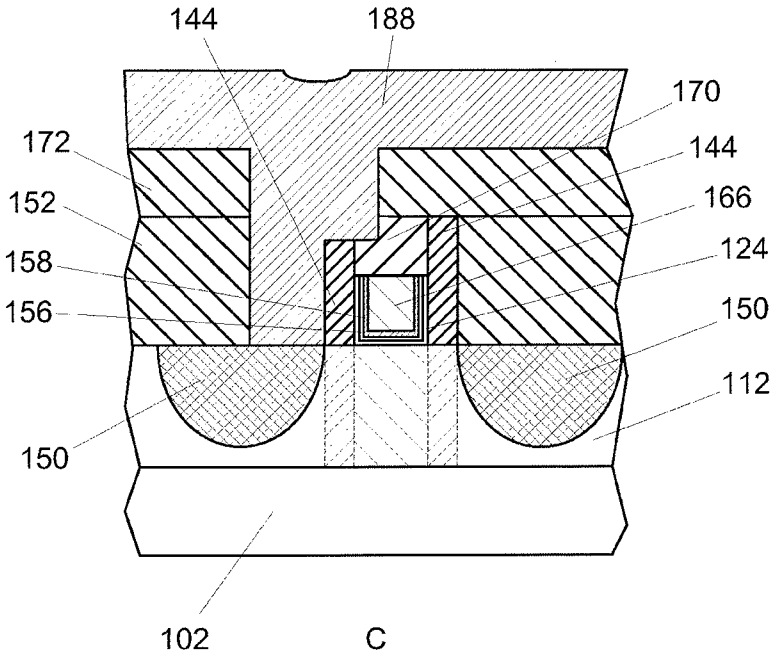

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188
170
172
144
152
166
158
124
156
150
112
150
102
C

FIG. 25

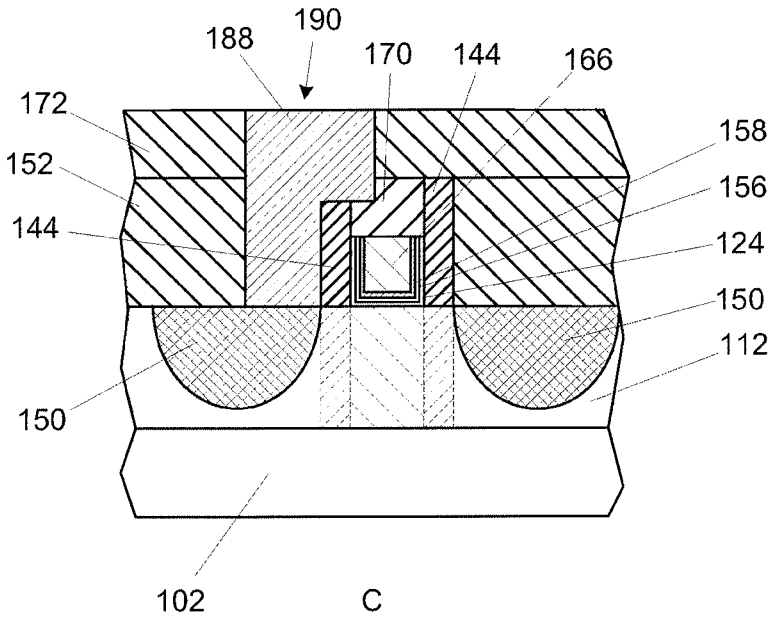

188
190
170
144
166
172
158
152
156
144
124
150
112
150
102
C

FIG. 26

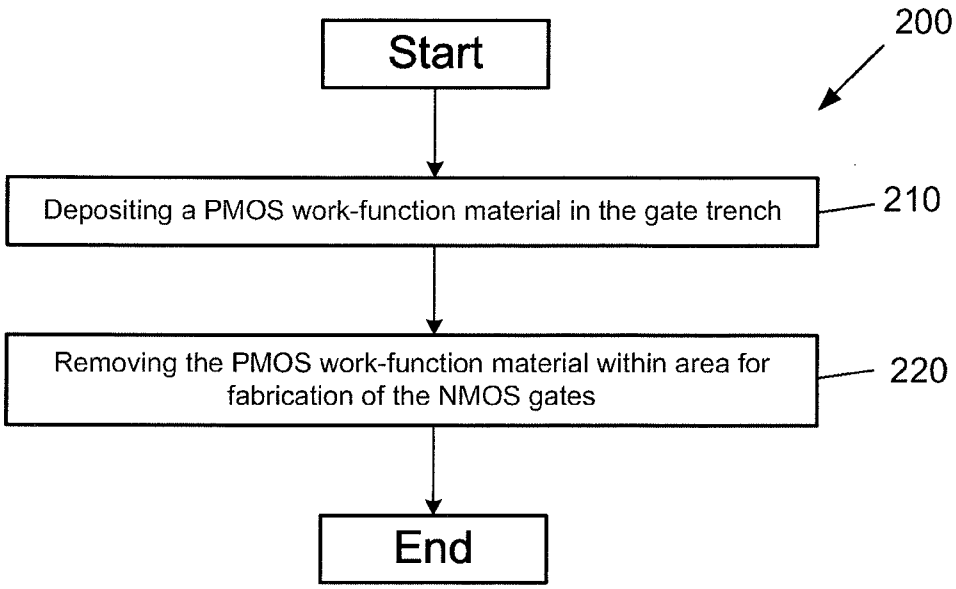

Start
200
Depositing a PMOS work-function material in the gate trench
210
Removing the PMOS work-function material within area for fabrication of the NMOS gates
220
End

FIG. 27

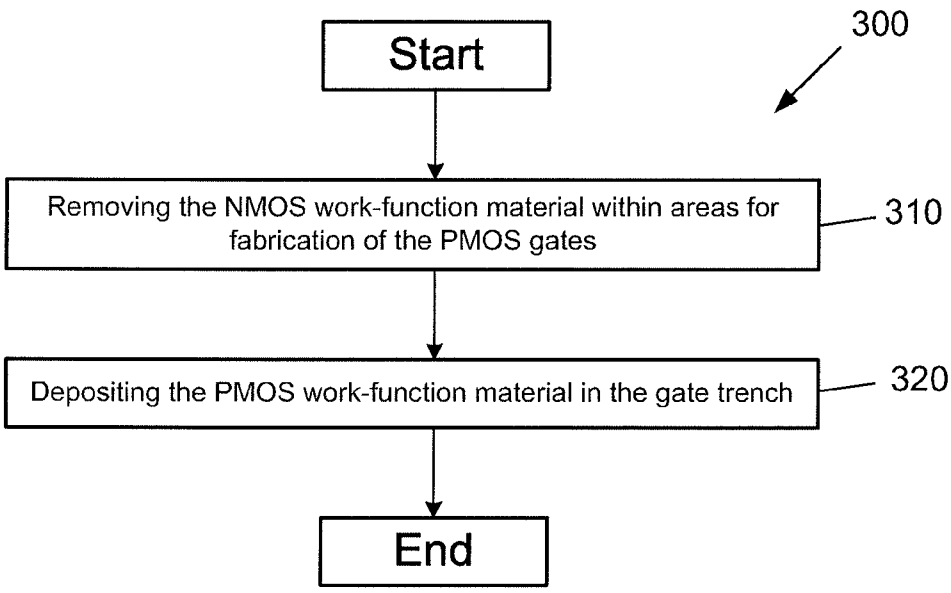

Start
300
Removing the NMOS work-function material within areas for fabrication of the PMOS gates
310
Depositing the PMOS work-function material in the gate trench
320
End

FIG. 28